

Magnetron Sputter System

Model: SA-VKM360

SA-VK M360 is a compact magnetron sputtering system. It features a small footprint, highly automated controls and easy-maintenance design, satisfying R&D requirements for universities and research institutes while effectively boosting R&D efficiency.



Feature

- High thin-film purity
- Excellent substrate adhesion
- Relatively high ionization rate
- Co-sputtering with mixed targets

Application

- Laser
- R&D
- Integrated circuit
- MEMS

Specifications:

Parameter	Descriptions
Number of Cathodes	4(max.)
Sputtering Power Supply	DC / RF / pulsed DC, freely switchable
Ion Source	RF & Kaufman & Hall ion source
Bias	RF / pulsed DC
Vacuum Sampling Chamber	optional
Pumping System	Cryopump / magnetically levitated turbo-molecular pump + Dry mechanical pump
Flow Control	Digital mass flow meter
Coating Uniformity	±3%
Coating Repeatability	±2%
Uniform Deposition Area	Ø150 mm(max.)
Ultimate Vacuum	1E-5Pa
Vacuum Measurement	Full-range vacuum gauge + Capacitance diaphragm gauge
Temperature Control Range	RT~300℃
Space Requirements(L×W×H,m)	1.6×2.75×1.8

Principle:

